

IN THE DRAWINGS

Please replace FIG. 1 with revised FIG. 1 to correct a drawing error, i.e., to replace the "28" representing the gate interlayer dielectric layer, which is the element between elements 20a and 22, with "24."

Please replace FIGS. 5-6 with revised FIGS. 5-6 to correct a drawing error, i.e., to replace "80b" with "88," which represents a resistor pattern.

REMARKS

Claims 1-20 are pending in the application.

Claims 4-20 are withdrawn from consideration.

Claims 1-3 are rejected.

The drawings filed on September 29, 2003 are objected to by the Examiner.

Claim 1 is rejected under 35 U.S.C. 102(b).

Claims 2 and 3 are rejected under 35 U.S.C. 103(a).

Claim 1 is currently amended.

No new matter is added.

Claims 1-3 remain in the case for consideration.

Applicant requests reconsideration and allowance of the claims in light of the above amendments and following remarks.

Drawings

FIG. 1 is objected to as the same numeral "28" is used to represent two different elements therein.

FIG. 1 is amended to replace the "28" representing the gate interlayer dielectric layer, which is the element between elements 20a and 22, with "24". The accompanying text in the Specification is also amended. No new matter is added.

Specification

The specification is amended to comply with the drawing amendment described above. No new matter is added.

Claim Rejection – 35 U.S.C. § 102

Claim 1 is rejected under 35 U.S.C. 102(b) as being anticipated by Applicant's Admitted Prior Art ("AAPA").

Applicants respectfully traverse the rejection.

Claim 1 has been amended to recite "*a resistor spacer disposed on sidewalls of the resistor pattern, ... wherein the space protrudes above resistor pattern.*" Support for this amendment is located, among other locations, on page 5, lines 14-16, and FIG. 7B, element 118b. No new matter has been added.

In contrast, AAPA does not teach, show, or suggest "*a spacer disposed on sidewalls of the resistor pattern, ...wherein the space protrudes above the resistor pattern,*" as recited in claim 1. In contrast, in FIGS. 1-6, the resistor pattern, e.g., 88 of the prior art is shown with no resistor spacers protruding above the resistor pattern. See page 2, line 31 to page 3, line 3 of the present application. Therefore, it is submitted that claim 1 is patentably distinguishable over the prior art and allowance of this claim is requested.

Claim Rejections – 35 U.S.C. § 103

Claims 2 and 3 are rejected under 35 U.S.C. 103(a) as being unpatentable over AAPA.

Applicants respectfully traverse the rejections.

Claims 2 and 3 depend from claim 1 and inherently include all of the limitations of the base claim. As discussed above, the prior art does not teach the limitations of the base claim much less the further embodiments of the dependent claim. Therefore, claims 2 and 3 are allowable for their dependency and their own merits.

In conclusion

For the foregoing reasons, reconsideration and allowance of claims 1-3 of the application as amended is solicited. The Examiner is encouraged to telephone the undersigned at (503) 222-3613 if it appears that an interview would be helpful in advancing the case.

Respectfully submitted,

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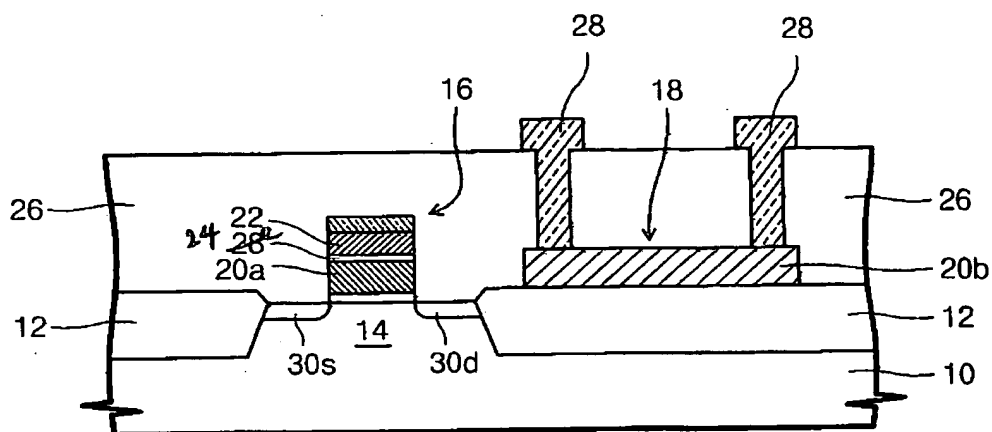
SEMICONDUCTOR DEVICE WITH RESISTOR PATTERN AND METHOD OF FABRICATING THE SAME

Attorney Docket No. 4591-330/Application No. 10/675,336

Annotated Sheet Showing Changes

1/3
Fig. 1

(PRIOR ART)

**Fig. 2**

(PRIOR ART)

